

- Flack, H. D. (1983). *Acta Cryst. A* **39**, 876–881.
 Gopal, R. & Calvo, C. (1972). *J. Solid State Chem.* **5**, 432–435.
 Harrison, W. T. A., Dussack, L. L. & Jacobson, A. J. (1994). *Inorg. Chem.* **33**, 6043–6049.
 Johnson, C. K. (1976). ORTEPII. Report ORNL-5138. Oak Ridge National Laboratory, Tennessee, USA.
 Larson, A. C. (1970). *Crystallographic Computing*, edited by F. R. Ahmed, S. R. Hall & C. P. Huber, pp. 291–294. Copenhagen: Munksgaard.
 Vandenborre, M., Sanchez, C. & Polit, A. (1985). *Nouv. J. Chem.* **9**, 511–518.
 Vaughrey, J. T., Harrison, W. T. A., Dussack, L. L. & Jacobson, A. J. (1994). *Inorg. Chem.* **33**, 4370–4375.
 Watkin, D. J., Carruthers, J. R. & Betteridge, P. W. (1990). CRYSTALS User Guide. Chemical Crystallography Laboratory, Univ. of Oxford, England.

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Low-Density Form of $NaGaSi_2O_6$

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Abstract

The structure of the title compound, gallium sodium silicate, is similar to that of jadeite ($NaAlSi_2O_6$). Comparison of the new crystal-structure refinement for $NaGaSi_2O_6$ with published refinements for eleven $NaM^{3+}Si_2O_6$ pyroxenes suggests that there are two different electronic states, $Ga(\alpha)$ and $Ga(\beta)$, for the octahedral Ga^{3+} ion. $Ga(\alpha)$ occurs in the Mn–Fe–Ga(α) series and $Ga(\beta)$ in the Al–Ga(β)–In series.

Comment

The structure of the title compound is isostructural with $NaAlSi_2O_6$, $NaCrSi_2O_6$ and $NaFeSi_2O_6$ (Clark, Appleman & Papike, 1969), $NaScSi_2O_6$ (Hawthorne & Grundy, 1973), $NaInSi_2O_6$ (Hawthorne & Grundy, 1974), $NaTiSi_2O_6$ (Ohashi, Fujita & Osawa, 1982), $NaGa(\alpha)Si_2O_6$ (Ohashi, Fujita & Osawa, 1983), $NaMnSi_2O_6$ (Ohashi, Osawa & Tsukimura, 1987) and $NaVSi_2O_6$ (Ohashi, Osawa & Sato, 1994).

The cell parameters of the $NaGa(\alpha)Si_2O_6$ pyroxene are: $a = 9.557(5)$, $b = 8.679(4)$, $c = 5.260(1)\text{ \AA}$, $\beta = 107.68(2)^\circ$ and $V = 415.7(3)\text{ \AA}^3$ (Ohashi *et al.*, 1983). The calculated density (D_x) is 3.91 Mg m^{-3} and is higher than that ($D_x = 3.89\text{ Mg m}^{-3}$) of the $NaGa(\beta)Si_2O_6$ pyroxene studied here. The atomic z coordinate for O1 [$z = 0.1312(7)$] of the $NaGa(\alpha)Si_2O_6$

pyroxene differs from that of the $NaGa(\beta)Si_2O_6$ pyroxene.

The O1–Si–O2 angle is the largest O–Si–O angle in the $NaM^{3+}Si_2O_6$ pyroxenes. This may be due in part to the greater repulsion between the more negatively charged non-bridging O atoms. As shown in Fig. 2, the O1–Si–O2 angles correlate with the differences d_{br-nbr} in such a way that they follow three different trends: the Sc–Ti–V–Cr series, the Mn–Fe–Ga(α) series and the Al–Ga(β)–In series, where $d_{br-nbr} = \langle Si-O_{br} \rangle - \langle Si-O_{nbr} \rangle$ (br = bridging, nbr = non-bridging), $\langle Si-O_{br} \rangle = 1/2(Si-O_{3A1} + Si-O_{3A2})$

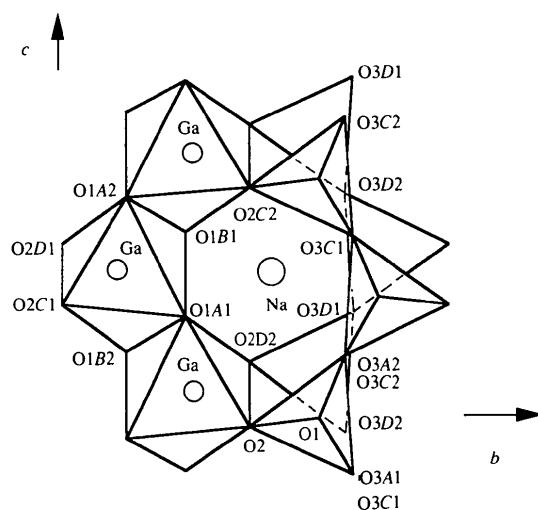


Fig. 1. Projection of the structure of $NaGaSi_2O_6$ onto the (100) plane. Atom labelling follows that used by Clark *et al.* (1969).

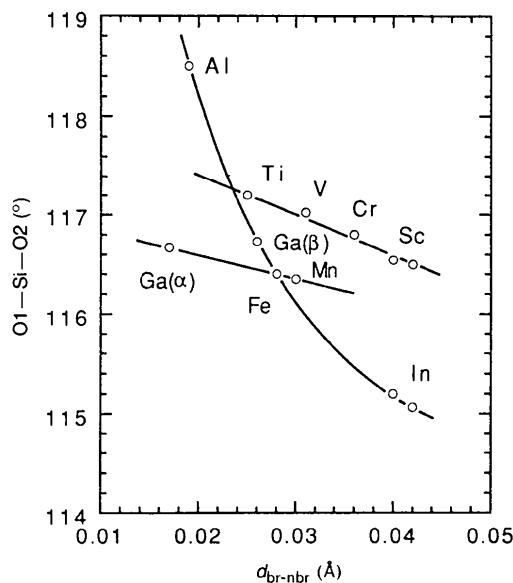


Fig. 2. The variation of the O1–Si–O2 angle ($^\circ$) with d_{br-nbr} (\AA) for the $NaM^{3+}Si_2O_6$ pyroxenes. Data are from Ohashi *et al.* (1994).

and $\langle \text{Si—O}_{\text{nbr}} \rangle = 1/2(\text{Si—O}1 + \text{Si—O}2)$. These trends suggest that there are two different electronic states for the octahedral Ga^{3+} ion.

Experimental

The title compound was prepared by solid-state reaction using belt-type high-pressure apparatus. A mixture of crystalline $\text{Na}_2\text{Si}_2\text{O}_5$, Ga_2O_3 and SiO_2 was sealed in a platinum capsule and maintained at 1770 K and 6 GPa for 5 h.

Crystal data

$\text{NaGaSi}_2\text{O}_6$	Mo $\text{K}\alpha$ radiation
$M_r = 244.88$	$\lambda = 0.7107 \text{ \AA}$
Monoclinic	Cell parameters from 22 reflections
$C2/c$	$a = 9.5573(5) \text{ \AA}$
	$b = 8.7019(2) \text{ \AA}$
	$c = 5.2705(3) \text{ \AA}$
	$\beta = 107.637(2)^\circ$
	$V = 417.73(4) \text{ \AA}^3$
$Z = 4$	$T = 296 \text{ K}$
	Prism
	$0.09 \times 0.04 \times 0.04 \text{ mm}$
	Colourless

Data collection

Enraf–Nonius CAD-4 diffractometer	$\theta_{\text{max}} = 31.5^\circ$
$\omega/2\theta$ scans	$h = 0 \rightarrow 14$
Absorption correction:	$k = 0 \rightarrow 12$
by integration from crystal shape	$l = -7 \rightarrow 7$
$T_{\text{min}} = 0.673$, $T_{\text{max}} = 0.771$	3 standard reflections monitored every 100 reflections for orientation and every 240 min for intensity
728 measured reflections	intensity decay: none
728 independent reflections	
649 observed reflections	
$[I > 1.5\sigma(I)]$	

Refinement

Refinement on F	Extinction correction:
$R = 0.018$	isotropic secondary
$wR = 0.029$	Extinction coefficient:
$S = 1.3$	1.83×10^{-6}
649 reflections	Atomic scattering factors
48 parameters	from International Tables for X-ray Crystallography (1974, Vol. IV)
$w = 1/\sigma^2(F)$	
$(\Delta/\sigma)_{\text{max}} < 0.005$	
$\Delta\rho_{\text{max}} = 0.480 \text{ e \AA}^{-3}$	
$\Delta\rho_{\text{min}} = -0.657 \text{ e \AA}^{-3}$	

Table 1. Fractional atomic coordinates and equivalent isotropic displacement parameters (\AA^2)

$$U_{\text{eq}} = (1/3) \sum_i \sum_j U_{ij} a_i^* a_j^* \mathbf{a}_i \cdot \mathbf{a}_j$$

	x	y	z	U_{eq}
Na	0	0.3005(1)	1/4	0.0125(3)
Ga	0	0.90189(3)	1/4	0.00471(5)
Si	0.29116(5)	0.09116(5)	0.2322(1)	0.0043(1)
O1	0.1120(2)	0.0779(1)	0.1334(3)	0.0057(3)
O2	0.3587(2)	0.2588(2)	0.3018(3)	0.0076(3)
O3	0.3527(1)	0.0097(2)	0.0076(2)	0.0068(3)

Table 2. Selected geometric parameters (\AA , $^\circ$)

Si tetrahedron	Ga octahedron		
Si—O1	1.636(1)	$\text{Ga}^{\text{ii}}—\text{O}1\text{A}1, \text{B}1^{\text{iii}}$	2.066(1)
Si—O2	1.592(1)	$\text{Ga}^{\text{ii}}—\text{O}1\text{A}2^{\text{i}}, \text{B}2^{\text{iv}}$	1.987(1)
Si—O3A1	1.634(2)	$\text{Ga}^{\text{ii}}—\text{O}2\text{C}1^{\text{v}}, \text{D}1^{\text{vi}}$	1.917(1)
Si—O3A2 ⁱ	1.646(1)	Mean of 6	1.990
Mean of 4	1.627		
O1—O2	2.748(2)	$\text{O}1\text{A}1 \cdots \text{O}1\text{B}1^{\text{iii}}$	2.773(2)
O1—O3A1	2.647(2)	$\text{O}2\text{C}1^{\text{v}} \cdots \text{O}2\text{D}1^{\text{vi}}$	2.914(2)
O1—O3A2 ⁱ	2.649(2)	$\text{O}1\text{A}1 \cdots \text{O}2\text{C}1^{\text{v}}$	2.802(2)
O2—O3A1	2.655(2)	$\text{O}1\text{A}1 \cdots \text{O}1\text{A}2^{\text{i}}$	2.964(2)
O2—O3A2 ⁱ	2.584(2)	$\text{O}1\text{A}2^{\text{i}} \cdots \text{O}2\text{C}1^{\text{v}}$	2.783(2)
O3A1—O3A2 ⁱ	2.641(2)	$\text{O}1\text{A}2^{\text{i}} \cdots \text{O}2\text{D}1^{\text{vi}}$	2.894(2)
Si—Si ⁱ	3.0760(7)	$\text{O}1\text{A}1 \cdots \text{O}1\text{B}2^{\text{iv}}$	2.565(2)
		$\text{Ga}^{\text{ii}} \cdots \text{Ga}^{\text{vii}}$	3.1401(2)
O1—Si—O2	116.73(7)	$\text{O}1\text{A}1—\text{Ga}^{\text{ii}}—\text{O}1\text{B}1^{\text{iii}}$	84.30(6)
O1—Si—O3A1	108.11(7)	$\text{O}1\text{A}1—\text{Ga}^{\text{ii}}—\text{O}2\text{C}1^{\text{v}}$	89.32(6)
O1—Si—O3A2 ⁱ	107.66(7)	$\text{O}1\text{A}1—\text{Ga}^{\text{ii}}—\text{O}1\text{A}2^{\text{i}}$	93.95(5)
O2—Si—O3A1	110.76(8)	$\text{O}1\text{A}1—\text{Ga}^{\text{ii}}—\text{O}1\text{B}2^{\text{iv}}$	78.47(5)
O2—Si—O3A2 ⁱ	105.89(7)	$\text{O}1\text{A}2^{\text{i}}—\text{Ga}^{\text{ii}}—\text{O}2\text{C}1^{\text{v}}$	90.94(5)
O3A1—Si—O3A2 ⁱ	107.25(7)	$\text{O}1\text{A}2^{\text{i}}—\text{Ga}^{\text{ii}}—\text{O}2\text{D}1^{\text{vi}}$	95.65(5)
		$\text{O}2\text{C}1^{\text{v}}—\text{Ga}^{\text{ii}}—\text{O}2\text{D}1^{\text{vi}}$	98.96(6)
Na antiprism			
Na—O1A1, B1 ⁱⁱⁱ	2.382(2)	$\text{Si}—\text{O}3—\text{Si}^{\text{xiv}}$	139.40(8)
Na—O2C2 ^{viii} , D2 ^{ix}	2.395(1)	$\text{Ga}^{\text{ii}}—\text{O}1—\text{Ga}^{\text{vii}}$	101.53(5)
Na—O3C1 ^{ix} , D1 ^x	2.417(2)	$\text{O}3^{\text{i}} \cdots \text{O}3 \cdots \text{O}3^{\text{xiv}}$	172.64(8)
Na—O3C2 ^{xii} , D2 ^{xiii}	2.777(2)		
Mean of 8	2.493		

Symmetry codes: (i) $x, -y, \frac{1}{2} + z$; (ii) $x, y - 1, z$; (iii) $-x, y, \frac{1}{2} - z$; (iv) $-x, -y, -z$; (v) $\frac{1}{2} - x, y - \frac{1}{2}, \frac{1}{2} - z$; (vi) $x - \frac{1}{2}, y - \frac{1}{2}, z$; (vii) $-x, 1 - y, -z$; (viii) $\frac{1}{2} - x, \frac{1}{2} - y, 1 - z$; (ix) $x - \frac{1}{2}, \frac{1}{2} - y, z - \frac{1}{2}$; (x) $\frac{1}{2} - x, \frac{1}{2} + y, \frac{1}{2} - z$; (xi) $x - \frac{1}{2}, \frac{1}{2} + y, z$; (xii) $\frac{1}{2} - x, \frac{1}{2} - y, -z$; (xiii) $x - \frac{1}{2}, \frac{1}{2} - y, \frac{1}{2} + z$; (xiv) $x, -y, z - \frac{1}{2}$.

Data were collected using Enraf–Nonius (1989) CAD-4 Software. The structure determination was initiated with the atomic parameters of $\text{NaAlSi}_2\text{O}_6$ given by Clark *et al.* (1969). All calculations were performed with the SDP program system (B. A. Frenz & Associates Inc., 1982).

Lists of structure factors and anisotropic displacement parameters have been deposited with the IUCr (Reference: OH1083). Copies may be obtained through The Managing Editor, International Union of Crystallography, 5 Abbey Square, Chester CH1 2HU, England.

References

- B. A. Frenz & Associates Inc. (1982). SDP Structure Determination Package. College Station, Texas, USA.
- Clark, J. R., Appleman, D. E. & Papike, J. J. (1969). *Mineral. Soc. Am. Spec. Pap.* **2**, 31–50.
- Enraf–Nonius (1989). CAD-4 Software. Version 5.0. Enraf–Nonius, Delft, The Netherlands.
- Hawthorne, F. C. & Grundy, H. D. (1973). *Acta Cryst.* **B29**, 2615–2616.
- Hawthorne, F. C. & Grundy, H. D. (1974). *Acta Cryst.* **B30**, 1882–1884.
- Ohashi, H., Fujita, T. & Osawa, T. (1982). *J. Jpn. Assoc. Mineral. Petro. Econ. Geol.* **77**, 305–309.
- Ohashi, H., Fujita, T. & Osawa, T. (1983). *J. Jpn. Assoc. Mineral. Petro. Econ. Geol.* **78**, 159–163.
- Ohashi, H., Osawa, T. & Sato, A. (1994). *Acta Cryst.* **C50**, 1652–1655.
- Ohashi, H., Osawa, T. & Tsukimura, K. (1987). *Acta Cryst.* **C43**, 605–607.